

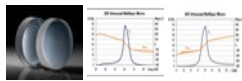
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25.4mm Dia. x 500mm EFL, 19nm (65eV), 5° EUV/XUV Attosecond Multilayer Concave Mirror

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UltraFast Innovations (UFI) EUV/XUV Attosecond Multilayer Mirrors



Stock **#16-767** **2 In Stock**

- 1 + **A\$4,032⁰⁰**

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General

Concave Mirror **Type:**

XUV65BW6 **Model Number:**

Supported Pulse Duration:

330 attoseconds

Physical & Mechanical Properties

25.40 ±0.13 **Diameter (mm):**

Commercial Polish **Back Surface:**

80 **Clear Aperture (%):**

6.35 ±0.20 **Edge Thickness ET (mm):**

Fine Ground **Edges:**

<1 **Surface Roughness (□):**

Optical Properties

EUV Multilayer (19nm) **Coating:**

19 **Design Wavelength DWL (nm):**

500.00 **Effective Focal Length EFL (mm):**

Fused Silica (Coming 7980) **Substrate: □**

5 **Angle of Incidence (°):**

Rs > 38% @ 65eV/19nm **Coating Specification:**

1,000.00 **Radius R₁ (mm):**

>38 **Reflection at DWL (%):**

λ/10 **Irregularity (P-V) @ 632.8nm:**

1,000.00 **Radius of Curvature (mm):**

Electrical

65 ±2 **Center Energy (eV):**

6 **Bandwidth (eV):**

Regulatory Compliance

Compliant **RoHS 2015:**

View **Certificate of Conformance:**

Compliant **Reach 235:**

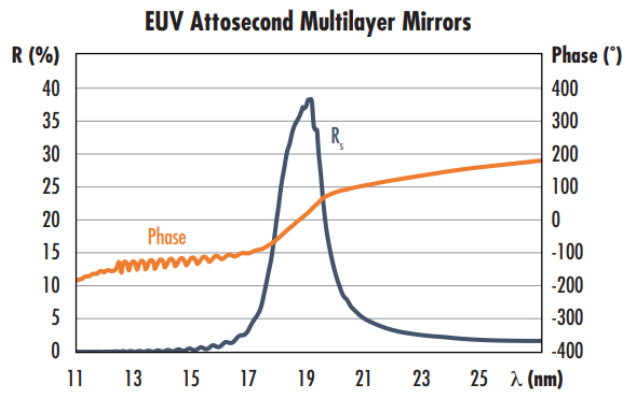
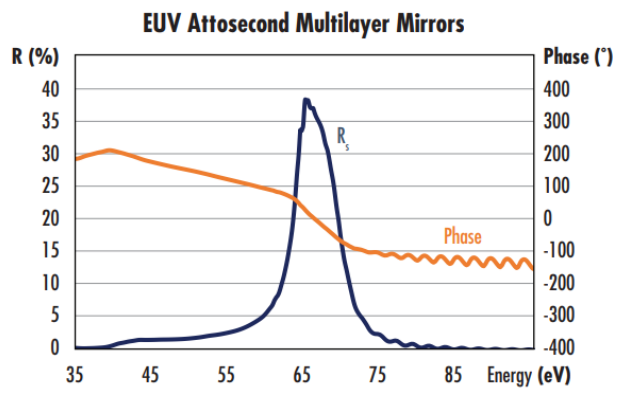
Product Details

- Designed for 330 Attosecond Pulses @65eV (19nm)
- Multilayer Coating with 38% Peak Reflectivity
- ≤1Å (Angstrom) Surface Roughness Superpolished Substrates
- [EUV Flat Mirrors](#) and [EUV Spherical Mirrors](#) Designed at 13.5nm Also Available
- No Minimum Order Quantities, No Coating Lot Charges
- [Platinum-Level 2022 Laser Focus World \(LFW\) Innovators Award](#)

UltraFast Innovations (UFI) Extreme Ultraviolet (EUV/XUV) Attosecond Multilayer Mirrors are designed for steering, focusing, and shaping attosecond pulses. Their multilayer coating is centered at 65eV (19nm) with a 6eV (1.8nm) bandwidth and provides a peak reflectivity of 38% for s-polarized light. These mirrors support EUV pulses with a temporal duration of 330 attoseconds. UFI Extreme Ultraviolet (EUV/XUV) Attosecond Mirrors are ideal for attosecond pulse generation and shaping based on high harmonic generation (HHG), free electron lasers (FELs), or other quantum optical applications.

Atomic precision ion beam deposition results in atomically-smooth coating layers. These mirrors allow for precision control of wavelength and spectral phase with high efficiency in a growing application space. Attosecond science pushes the limits of ultrafast lasers, providing access to some of the most fundamental scientific processes like the motion of electrons. EUV Mirrors are also known as XUV/Soft X-Ray Mirrors. The physical principal behind EUV Attosecond Multilayer Mirrors is the interference of reflected and scattered EUV radiation from each interface of the multilayer stack. Flat and concave mirrors with a 25.4mm diameter are available; please contact us if your application requires an EUV multilayer mirror with a customized center energy, bandwidth, or other specifications.

Technical Information



Special Handling

These optics require special handling to avoid damage and ensure long-term performance. Proper handling, cleaning, and storage are essential to maintain optical quality. Explore our [Optics Cleaning Resources](#) for step-by-step guides and best practices. For personalized assistance, [Email us](#) or [Chat](#) with our technical support team.



Component Handling Tools

Compatible Mounts